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A Comparative Study of Wet Etching and Contacts on $(\overline{2}01)$ and (010)Oriented β -Ga₂O₃

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ABSTRACT

We report on the effect of β -Ga₂O₃ crystal orientation on wet etching and Ohmic contact formation. The photochemical etching rate in KOH solutions of ($\overline{2}01$) oriented, n-type bulk single crystals grown by the edge-defined film-fed growth method is ~3-4 times higher than for the (010) planes. The activation energy for etching was 0.498 eV and 0.424 eV for ($\overline{2}01$) and (010) orientations, respectively, suggesting the etching is reaction-limited with the same ratelimiting step. Ti (200 Å)/Au (1500 Å) metallization deposited on the two different orientations and annealed at 450 °C showed Ohmic current-voltage (*I-V*) behavior for ($\overline{2}01$) but rectifying characteristics for (010). For (010) Ga₂O₃, there exists 2 types of surfaces having Ga and O atomic densities of 0.58 and 0.87×10¹⁵ cm⁻², respectively. By contrast, for ($\overline{2}01$) Ga₂O₃ surfaces, there exist 2 types of surface, with each type terminated with only Ga or O. If the surface is Download English Version:

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